What is claimed is:

1. An organic electro-luminescent display device, comprising:
a glass substrate;
an optic-compensation film of transparent dielectric material formed on the surface of the glass substrate;
an anode layer formed on the optic-compensation film;
a laminated body of organic material formed on the anode layer; and
a cathode layer formed on the laminated body.

2. The organic electro-luminescent display device as claimed in claim 1, wherein the optic-compensation film is silicon nitride (SiNx).

3. The organic electro-luminescent display device as claimed in claim 1, wherein the optic-compensation film is of 100~3000Å thickness.

4. The organic electro-luminescent display device as claimed in claim 1, wherein the optic-compensation film promotes transparency of red light to approximately 90%.

5. The organic electro-luminescent display device as claimed in claim 1, wherein the anode layer is ITO.

6. The organic electro-luminescent display device as claimed in claim 1, wherein the laminated body comprises:
a hole-injecting layer formed on the anode layer;

an organic luminescent material layer formed on the hole-injecting layer; and

an electron-injecting layer formed on the organic luminescent material layer.

7. The organic electro-luminescent display device as claimed in claim 1, wherein the organic electro-luminescent display device is an OLED device or a PLED device.

8. A method of forming an organic electro-luminescent display device, comprising:

providing a glass substrate;

forming an optic-compensation film of transparent dielectric material on the surface of the glass substrate, in which the transparent nature of the optic-compensation film is not limited to light of a specific wavelength;

forming an anode layer on the optic-compensation film;

forming a laminated body of organic material on the anode layer; and

forming a cathode layer on the laminated body.

9. The method of forming an organic electro-luminescent display device as claimed in claim 8, wherein the optic-compensation film is silicon nitride (SiNx).

10. The method of forming an organic electro-luminescent display device as claimed in claim 8, wherein the optic-compensation film is of 100~3000Å thickness.

11. The method of forming an organic electro-luminescent display device as claimed in claim 8, wherein

the optic-compensation film promotes transparency of red light to approximately 90%.

12. The method of forming an organic electro-luminescent display device as claimed in claim 8, wherein the optic-compensation film increases the transparency of red light.

13. The method of forming an organic electro-luminescent display device as claimed in claim 8, wherein the anode layer is ITO.

14. The method of forming an organic electro-luminescent display device as claimed in claim 8, wherein the laminated body comprises:

a hole-injecting layer formed on the anode layer;

an organic luminescent material layer formed on the hole-injecting layer; and

an electron-injecting layer formed on the organic luminescent material layer.

15. The method of forming an organic electro-luminescent display device as claimed in claim 8, wherein the organic electro-luminescent display device is an OLED device or a PLED device.